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## (54) METHOD AND INSTRUMENT FOR MEASUIRNG HARDNESS AND ELASTIC MODULUS OF THIN FILM (57) Abstract:

PROBLEM TO BE SOLVED: To provide a method and instrument for measuring the hardness and elastic modulus of a thin film, capable of accurately and precisely measuring a contact area by merely calculating work without generating a measuring error and capable of accurately evaluating the mechanical characteristics (harness and elastic modulus) of the thin film.

SOLUTION: In the method and apparatus for measuring the hardness and elastic modulus of the thin film, by pressing a pressure element to the thin film to be measured to change load quasi-statically, an x-value is calculated from a work Wt applied to the thin film of the pressure element at the loading time and a work W applied to the pressure element of the thin film at the unloading time by equation (3). H/E=0.215-0.234x ( $0\le x\le 0.8$ )...(1) =0.16-0.16x ( $0.8\le x\le 1.0$ )...(2) x=(Wt-Wu)/Wt...(3)  $H=Pmax/A...(4)E=(\pi/2A)1/2dP/dh...(5)Based on the x-value, <math>H/E$  ratio is calculated from equation (1) or (2) and the contact area A is calculated from t H/E ratio and equations (4), (5) [where, H is hardness (Gpa) of the thin film, E is elastic modulus (Gpa) of the thin film, P is the maximum load (load at the maximum displacement), A is the contact area of the pressure element at the maximum load, h is the displacement of the pressure element (push-in depth) and dP/dh is the inclination of an unloading curve at the maximum load] and are substituted in the equations (4), (5) to calculate the hardness and elastic modulus of the thin film.

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